

Second edition
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Hardmetals — Metallographic determination of microstructure —

Part 2: Measurement of WC grain size

*Métaux-durs — Détermination métallographique de la
microstructure —*

Partie 2: Mesurage de la taille des grains de WC



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ISO copyright office
CP 401 • Ch. de Blandonnet 8
CH-1214 Vernier, Geneva
Phone: +41 22 749 01 11
Email: copyright@iso.org
Website: www.iso.org

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Foreword

ISO (the International Organization for Standardization) is a worldwide federation of national standards bodies (ISO member bodies). The work of preparing International Standards is normally carried out through ISO technical committees. Each member body interested in a subject for which a technical committee has been established has the right to be represented on that committee. International organizations, governmental and non-governmental, in liaison with ISO, also take part in the work. ISO collaborates closely with the International Electrotechnical Commission (IEC) on all matters of electrotechnical standardization.

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This document was prepared by Technical Committee ISO/TC 119, *Powder metallurgy*, Subcommittee SC 4, *Sampling and testing methods for hardmetals*, in collaboration with the European Committee for Standardization (CEN) Technical Committee CEN/SS M11, *Powder metallurgy*, in accordance with the Agreement on technical cooperation between ISO and CEN (Vienna Agreement).

This second edition cancels and replaces the first edition (ISO 4499-2:2008), which has been technically revised.

The main changes compared to the previous edition are as follows:

- former 3.1 has been removed;
- [3.2](#) has been expanded;
- in [Clause 5](#), “Electron back scatter diffraction (EBSD)” has been added;
- in [7.2.1](#), the list has been revised;
- in [7.3.3](#), [Table 1](#), row “Electron back scatter diffraction” has been added and in the row “Scanning electron microscope”, the value for the “Minimum visible intercept length” has been corrected from 200 nm into 400 nm.

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